a1 Cont'd

7. (Amended) The plasma display panel of Claim 1,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

a2

13. (Amended) The plasma display panel of Claim 8,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

a3

17. (Amended) The plasma display panel of Claim 14,

wherein the metal or the metal oxide that coats the surface of each Ag particle forms a layer with an average thickness in a range of 01 μm to 1μm inclusive.

18. (Amended) The plasma display panel of Claim 14,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

a4

21. (Amended) The plasma display panel of Claim 19,

wherein the first plate, or both the first plate and the second plate are glass plates.

22. (Amended) A display apparatus comprising:

the plasma display panel of Claim 1; and

a driving circuit that drives the plasma display panel.

a5

31. (Amended) The manufacturing method for a plasma display panel of Claim 29, wherein in the electrode formation step, the electrodes made of the silver alloy are formed, by forming the silver alloy into a film by a sputtering method, and patterning the formed film.

32. (Amended) The manufacturing method for a plasma display panel of Claim 29, wherein in the electrode formation step, the electrodes made of the silver alloy are formed, by (a) forming a film containing the silver alloy and a glass frit, (b) patterning the formed film, and (c) baking the patterned film.

a6

34. (Amended) The manufacturing method for a plasma display panel of Claim 29, wherein in the electrode formation step, the electrodes made of the silver alloy are formed, by applying a paste containing the silver alloy and a glass frit in electrode shapes, and baking the applied paste.

a9

48. (Amended) The manufacturing method for a substrate for use in a plasma display panel of Claim 46,

wherein in the etching step, the glass plate is etched by impregnating the surface of the glass plate with a liquid containing fluorine.

49. (Amended) The manufacturing method for a substrate for use in a plasma display panel of Claim 46,

wherein in the etching step, the glass plate is etched so that a concentration of metal ions that exist in a vicinity of a surface of the etched substrate is 1000ppm or less, the metal ions possessing reducing action on Ag ions.

50. (Amended) The manufacturing method for a substrate for use in a plasma display panel of Claim 46,

wherein in the etching step, the glass plate is etched so that a total concentration of tin with less than four valence electrons, manganese with less than four valence electrons, iron with less than two valence electrons, and indium with less than two valence electrons that exist in a vicinity of a surface of the etched substrate is 1000ppm or less.

51. (Amended) The manufacturing method for a substrate for use in a plasma display panel of Claim 46,

wherein the etching step is followed by a polishing step for polishing the surface of the etched substrate.

55. (Amended) The manufacturing method for a substrate for use in a plasma display panel of Claim 52,

wherein in the deactivating step, the glass plate is processed so that a total concentration of tin with less than four valence electrons, manganese with less than four valence electrons, iron with less than two valence electrons, and indium with less than two valence electrons that exist in a region of 5μm in depth from a surface of the substrate is 1000ppm or less.

Please add the following newly-drafted Claims 56-90.

56. (New) The plasma display panel of Claim 2,

wherein the first electrodes are constructed by forming each electrode on a transparent electrode film.

a9 Cont'd

57. (New) The plasma display panel of Claim 3,

wherein the first electrodes are constructed by forming each electrode on a transparent electrode film.

58. (New) The plasma display panel of Claim 4,

wherein the first electrodes are constructed by forming each electrode on a transparent electrode film.

59. (New) The plasma display panel of Claim 5,

wherein the first electrodes are constructed by forming each electrode on a transparent electrode film.

60. (New) The plasma display panel of Claim 2,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

61. (New) The plasma display panel of Claim 3,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

62. (New) The plasma display panel of Claim 4,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

a9 Cont.d

63. (New) The plasma display panel of Claim 5,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

64. (New) The plasma display panel of Claim 9,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

65. (New) The plasma display panel of Claim 10,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

66. (New) The plasma display panel of Claim 11,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

67. (New) The plasma display panel of Claim 12,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

a9 Cont'd

68. (New) The plasma display panel of Claim 15,

wherein the metal or the metal oxide that coats the surface of each Ag particle forms a layer with an average thickness in a range of 01 μm to 1μm inclusive.

69. (New) The plasma display panel of Claim 16,

wherein the metal or the metal oxide that coats the surface of each Ag particle forms a layer with an average thickness in a range of 01 μm to 1μm inclusive.

70. (New) The plasma display panel of Claim 15,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

71. (New) The plasma display panel of Claim 16,

wherein the first electrodes are covered with a dielectric layer made of a dielectric glass material.

72. (New) The plasma display panel of Claim 20,

wherein the first plate, or both the first plate and the second plate are glass plates.

73. (New) A display apparatus comprising:

the plasma display panel of Claim 3; and

a driving circuit that drives the plasma display panel.

74. (New) A display apparatus comprising:

the plasma display panel of Claim 8; and

a driving circuit that drives the plasma display panel.

a9 Cont'd

75. (New) A display apparatus comprising:

the plasma display panel of Claim 10; and

a driving circuit that drives the plasma display panel.

76. (New) A display apparatus comprising:

the plasma display panel of Claim 14; and

a driving circuit that drives the plasma display panel.

77. (New) A display apparatus comprising:

the plasma display panel of Claim 19; and

a driving circuit that drives the plasma display panel.

78. (New) A display apparatus comprising:

the plasma display panel of Claim 20; and

a driving circuit that drives the plasma display panel.

79. (New) The manufacturing method for a plasma display panel of Claim 30, wherein in the electrode formation step, the electrodes made of the silver alloy are formed, by forming the silver alloy into a film by a sputtering method, and patterning the formed film.

80. (New) The manufacturing method for a plasma display panel of Claim 30, wherein in the electrode formation step, the electrodes made of the silver alloy are formed, by (a) forming a film containing the silver alloy and a glass frit, (b) patterning the formed film, and (c) baking the patterned film.

a9 cont'd

81. (New) The manufacturing method for a plasma display panel of Claim 30, wherein in the electrode formation step, the electrodes made of the silver alloy are formed, by applying a paste containing the silver alloy and a glass frit in electrode shapes, and baking the applied paste.

82. (New) The manufacturing method for a substrate for use in a plasma display panel of Claim 47, wherein in the etching step, the glass plate is etched by impregnating the surface of the glass plate with a liquid containing fluorine.

83. (New) The manufacturing method for a substrate for use in a plasma display panel of Claim 47, wherein in the etching step, the glass plate is etched so that a concentration of metal ions that exist in a vicinity of a surface of the etched substrate is 1000ppm or less, the metal ions possessing reducing action on Ag ions.

84. (New) The manufacturing method for a substrate for use in a plasma display panel of Claim 48, wherein in the etching step, the glass plate is etched so that a concentration of metal ions that exist in a vicinity of a surface of the etched substrate is 1000ppm or less, the metal ions possessing reducing action on Ag ions.

85. (New) The manufacturing method for a substrate for use in a plasma display panel of Claim 47, wherein in the etching step, the glass plate is etched so that a total concentration

a9 cont'd

of tin with less than four valence electrons, manganese with less than four valence electrons, iron with less than two valence electrons, and indium with less than two valence electrons that exist in a vicinity of a surface of the etched substrate is 1000ppm or less.

86. (New) The manufacturing method for a substrate for use in a plasma display panel of Claim 48,

wherein in the etching step, the glass plate is etched so that a total concentration of tin with less than four valence electrons, manganese with less than four valence electrons, iron with less than two valence electrons, and indium with less than two valence electrons that exist in a vicinity of a surface of the etched substrate is 1000ppm or less.

87. (New) The manufacturing method for a substrate for use in a plasma display panel of Claim 47,

wherein the etching step is followed by a polishing step for polishing the surface of the etched substrate.

88. (New) The manufacturing method for a substrate for use in a plasma display panel of Claim 48,

wherein the etching step is followed by a polishing step for polishing the surface of the etched substrate.

89. (New) The manufacturing method for a substrate for use in a plasma display panel of Claim 53,

wherein in the deactivating step, the glass plate is processed so that a total concentration of tin with less than four valence electrons, manganese with less than four valence

a9 Concl

electrons, iron with less than two valence electrons, and indium with less than two valence electrons that exist in a region of 5μm in depth from a surface of the substrate is 1000ppm or less.

90. (New) The manufacturing method for a substrate for use in a plasma display panel of Claim 54,

wherein in the deactivating step, the glass plate is processed so that a total concentration of tin with less than four valence electrons, manganese with less than four valence electrons, iron with less than two valence electrons, and indium with less than two valence electrons that exist in a region of 5μm in depth from a surface of the substrate is 1000ppm or less.